

Abstract

The invention relates to a method for manufacturing a nanostructure (150) in-situ at at least one predetermined point (A,B) on a supporting carrier (110). comprising choosing a suitable material for a substrate in the carrier (150), creating said substrate, preparing a template (115) on the substrate so that the template covers said predetermined point (A, B). The template is given a proper shape according to the desired final shape of the nanostructure, and a film (140) of nanosource material with desired dimensions is formed on the template (115), and the film (140) of nanosource material is made to restructure from a part of the template, thus forming the desired nanostructure (150). Suitably, the template (115) comprises a first (120) and a second (130) area which have different properties with respect to the nanosource material.